



RECEIVED

OCT 10 2002

TC 1700

Patent

Attorney's Docket No. 015290-426

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )  
)  
William Frederick BOSCH ) Group Art Unit: 1765  
)  
Application No.: 09/607,922 ) Examiner: L. T. Umez-Eronini  
)  
Filed: June 30, 2000 ) Confirmation No.: 9687  
)  
For: SEMICONDUCTOR PROCESSING )  
EQUIPMENT HAVING IMPROVED )  
PARTICLE PERFORMANCE )

**AMENDMENT/REPLY TRANSMITTAL LETTER**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

- ☐ A Petition for Extension of Time is also enclosed.
- ☐ A Terminal Disclaimer and a check for ☐ \$55.00 (2814) ☐ \$110.00 (1814) to cover the requisite Government fee are also enclosed.
- ☐ Also enclosed is \_\_\_\_\_.
- ☐ Small entity status is hereby claimed.
- ☐ Applicant(s) request continued examination under 37 C.F.R. § 1.114 and enclose the ☐ \$370.00 (2801) ☐ \$740.00 (1801) fee due under 37 C.F.R. § 1.17(e).
- ☐ Applicant(s) previously submitted \_\_, on \_\_, for which continued examination is requested.
- ☐ Applicant(s) request suspension of action by the Office until at least \_\_, which does not exceed three months from the filing of this RCE, in accordance with 37 C.F.R. § 1.103(c). The required fee under 37 C.F.R. § 1.17(i) is enclosed.
- ☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (146/246) is also enclosed.
- ☐ No additional claim fee is required.



RECEIVED

OCT 10 2002

TC 1700

Patent

Attorney's Docket No. 015290-426

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )  
William Frederick BOSCH ) Group Art Unit: 1765  
Application No.: 09/607,922 ) Examiner: L. T. Umez-Eronini  
Filed: June 30, 2000 ) Confirmation No.: 9687  
For: SEMICONDUCTOR PROCESSING )  
EQUIPMENT HAVING IMPROVED )  
PARTICLE PERFORMANCE )

AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Official Action mailed August 13, 2002, please amend the above-identified application as follows.

IN THE CLAIMS:

Please replace Claim 14 and add new Claims 35 and 36 as follows:

14. (Amended) A method of processing semiconductor substrates and reducing particle contamination during processing of the substrates, the method comprising:

(a) placing at least one substrate on a substrate holder in an interior space of a vacuum processing chamber, the processing chamber comprising a plasma reactor and including at least one ceramic part made of a non-oxide ceramic material and having a machined and/or sintered surface exposed to the interior space, the exposed surface having been treated to reduce particles of the non-oxide ceramic material attached to the exposed

10/09/2002 NGUYEN 00000047 024800 09607922

01 FC:103

35.00 CH